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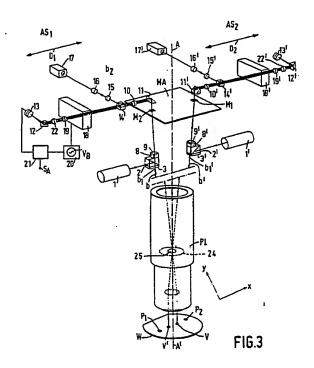
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- Apparatus for projecting a mask pattern on a substrate.
- The system (PL) is described, which apparatus comprises a device for aligning a substrate alignment mark (P₁; P₂) with respect to a mask alignment mark (M₁; M₂), the projection lens system (PL) forming part of the alignment device. A correction element (25) is arranged in this system (PL) to compensate for the fact that this system (PL) is not optimised for the wavelength of the alignment beam (b).



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EUROPEAN SEARCH REPORT

EP 90 20 0925

Category	Citation of document with i of relevant pa	ndication, where appropriate, ssages	Relevant to claim	CLASSIFICATION OF THE APPLICATION (Int. CL5)	
D,A	EP-A-237109 (ASM LITHOGRAPHY) * pages 11 - 25; claim 10; figures * & US-A-4778275		1, 3, 4, 7, 10 11, 13, 16-19	G03F9/00	
4	DE-A-1904504 (WESTERN ELECTRIC) * pages 5 - 9; figures *		1, 3		
D,A	DE-A-2608176 (LENINGRA MECHANIKI I OPTIKI ET A * page 11, last 3 line		12		
				TECIINICAL FIELDS SEARCHED (Int. CL5)	
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The present search report has been drawn up for all claims			÷		
Fisce of search Date of completion of the search			Examiner		
	THE HAGUE	15 JUNE 1990	HER	YET C.D.	
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